CLAIMS

What is claimed is:

- 1. A field emission device, comprising: a silicon substrate having an emitter electrode formed in a surface portion thereof; an insulating layer formed on said emitter electrode and having a nano hole to expose said emitter electrode; an emitter formed on said emitter electrode exposed through said nano hole; and a gate electrode formed on said insulating layer.
- 2. The field emission device as claimed in claim 1, wherein said emitter electrode is formed by an impurity implantation.
- 3. The field emission device as claimed in claim 1, further comprising a catalyst layer formed between said emitter electrode and said emitter.
- 4. The field emission device as claimed in claim 3, wherein said catalyst layer is made of a transition metal.
- 5. The field emission device as claimed in claim 1, wherein said emitter is formed of any one of carbon nanotube, a nano grain film and a metal tip.